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SERIAL NUMBER	REQUEST DATE	FIRST NAMED APPLICANT	ATTORNEY DOCKET NO.
10/552,606	3/24/06	TOMOHaru NAKANO, ET AL.	052463

Title: **POLISHING LIQUID FOR CMP PROCESS AND
POLISHING METHOD**

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Art Unit	Paper Number
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Correspondence Address:

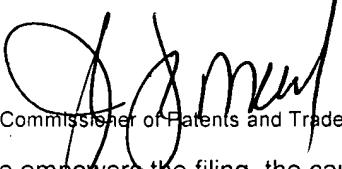
SHUJI YOSHIZAKI
WESTERMAN, HATTORI, DANIELS & ADRIAN LLP.
1250 CONNECTICUT AVE., STE 700
WASHINGTON, D.C. 20036

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LICENSE FOR FOREIGN FILING

[Title 35, United States Code (1952) Sections 184, 185, 186]



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Petitioner: NAKANO, et al. :DECISION ON REQUEST
Petition No.: 10/552,606 :UNDER 37 CFR 5.25
Petition Filing Date: 24 March 2006
Docket No.: 052463

Title: POLISHING LIQUID FOR CMP PROCESS AND POLISHING METHOD

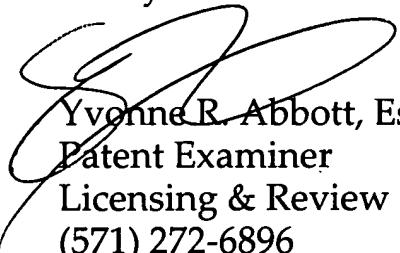
This is a decision on the petition for retroactive foreign filing license.

It has been determined that a retroactive license for foreign filing under 35 U.S.C. 184 be granted with respect to the filing(s) listed below. The petition complies with 37 C.F.R. 5.25 in that there is an adequate showing that the subject matter in question was not under secrecy order, that the license was diligently sought, and that the material was filed abroad without the required license under 37 C.F.R. 5.11 through error and without deceptive intent.

Foreign Filing Location

Date

Japan	07 May 2004
Taiwan	07 May 2004
Malaysia	07 May 2004


Yvonne R. Abbott, Esq.
Patent Examiner
Licensing & Review
(571) 272-6896